

**Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

**Listing of Claims:**

1. (original) A semiconductor processing module comprising:
  - a housing adapted to enclose a semiconductor wafer;
  - an ultraviolet radiation source disposed within the housing; and
  - a treatment medium disposed within the housing.
2. (original) The module of claim 1, wherein the ultraviolet radiation source comprises an ultraviolet lamp.
3. (original) The module of claim 1, wherein the treatment medium comprises ambient air.
4. (original) The module of claim 1, wherein the treatment medium comprises oxygen.
5. (original) The module of claim 1, wherein the treatment medium comprises ozone.
6. (original) The module of claim 1, further comprising a medium supply system disposed within the housing.

7. (original) The module of claim 6, wherein the medium supply system comprises a gas inlet.
8. (original) The module of claim 6, wherein the medium supply system comprises an ozone generator.
9. (original) The module of claim 1, further comprising a medium conditioning system disposed within the housing.
10. (original) The module of claim 9, further comprising a medium supply system disposed within the medium conditioning system.
11. (original) The module of claim 9, wherein the medium conditioning system is adapted to induce a partial vacuum within the housing.
12. (original) The module of claim 9, wherein the treatment medium is a vacuum induced by the medium conditioning system.
13. (original) The module of claim 9, wherein the medium conditioning system comprises a filtration system.

Claims 14-26 (canceled).

27. (original) A system for remediating organic contaminants from a copper seed layer deposited on an upper surface of a semiconductor wafer, the system comprising:

a housing adapted to receive and enclose the semiconductor wafer;

an ultraviolet radiation source disposed within the housing and adapted to expose the semiconductor wafer to ultraviolet radiation;

an ozone generator adapted to supply ozone into the housing as a treatment medium for the semiconductor wafer; and

a conditioning system disposed within the housing and adapted to filter contaminants from the ozone.